



(3)

Docket No. 740756-2092

OK Hall  
#17C  
MH  
5-10-02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT Application of: )

Koichiro TANAKA )

Art Unit: 2877

Application Serial No. 09/481,396 )

Examiner A. Rodriguez

Filed: January 12, 2000 )

For: LASER IRRADIATION APPARATUS )

CERTIFICATE OF MAILING

AMENDMENT UNDER 37 C.F.R. §1.312

Box: ISSUE FEE

Honorable Commissioner for Patents  
Washington, D. C. 20231

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231, on 3-18-02

Sir:

Please enter the following amendment for the above-identified application, a Notice of Allowance for which was mailed December 18, 2001.

IN THE SPECIFICATION:

On page 17, the fourth full paragraph, please substitute therefor the following paragraph. A marked-up copy of the substitute paragraph is attached hereto.

C1  
When YAG laser is used for the purpose of crystallizing a film containing silicon as a main component, a wave length having at least one of the second to the fourth harmonic waves is used. Further, when YAG laser is used for the purpose of activating or/and laser annealing, a wave length containing one or a plurality of the basic wave to the fourth harmonic waves is used.

On page 23, the first full paragraph, please substitute therefor the following paragraph. A marked-up copy of the substitute paragraph is attached hereto.

C2  
As the laser beam generating unit 801, the unit for oscillating XeCl excimer laser (wavelength 309 nm) is used. Other than this, excimer laser such as KrF excimer laser

NVA218130.1

OK to Enter